

**In the Claims:**

**Claim 1 (currently amended):** A method comprising steps of:  
forming a layer over a transistor gate region and a field oxide region;  
forming a doping barrier above said layer over said field oxide region;  
doping said layer over said transistor gate region with a dose of a first dopant,  
wherein said dose of said first dopant is a dosage greater than required to result in said  
layer over said transistor gate region having transistor gate electrical properties;  
removing said doping barrier;  
doping said layer over said transistor gate region and said field oxide region with a  
second dopant so as to form a high resistivity resistor in said layer over said field oxide  
region without affecting said transistor gate electrical properties;  
doping a portion of said layer over said field oxide region with a third dopant so as  
to form a high-doped region in said layer over said field oxide region;  
fabricating a contact region for said high resistivity resistor over said high-doped  
region.

**Claim 2 (canceled).**

**Claim 3 (original):** The method of claim 1 wherein said layer comprises  
polycrystalline silicon.

**Claim 4 (previously presented):** The method of claim 1 wherein said transistor gate region is a gate of an PFET.

**Claim 5 (previously presented):** The method of claim 1 wherein said transistor gate region is a gate of an NFET.

**Claim 6 (original):** The method of claim 1 wherein said field oxide comprises silicon dioxide.

**Claim 7 (original):** The method of claim 1 wherein said first dopant is an N type dopant.

**Claim 8 (original):** The method of claim 7 wherein said N type dopant comprises phosphorous.

**Claim 9 (previously presented):** The method of claim 1 wherein said first dopant comprises phosphorous at a dose of approximately  $6.5 \times 10^{15}$  atoms per square centimeter.

**Claim 10 (original):** The method of claim 1 wherein said second dopant is a P type dopant.

**Claim 11 (original):** The method of claim 10 wherein said P type dopant comprises boron.

**Claim 12 (previously presented):** The method of claim 1 wherein said second dopant comprises boron at a dose of approximately  $1.0 \times 10^{15}$  atoms per square centimeter.

**Claim 13 (currently amended):** The method of claim 2 1 wherein said contact region comprises a silicide.

**Claim 14 (currently amended):** A method comprising steps of:  
depositing a polycrystalline silicon layer on a chip, said polycrystalline silicon layer including a gate region and a resistor region;  
forming a doping barrier above said polycrystalline silicon layer so as to prevent doping of said resistor region of said polycrystalline silicon layer;  
doping said polycrystalline silicon layer with a dose of a first dopant, wherein said dose of said first dopant is a dosage greater than required to result in said layer over said gate region having transistor gate electrical properties;  
removing said doping barrier;

doping said polycrystalline silicon layer with a second dopant so as to form a high resistivity resistor in said resistor region of said polycrystalline silicon layer without affecting said transistor gate electrical properties;

doping a portion of said resistor region of said polycrystalline silicon layer with a third dopant so as to form a high-doped region in said resistor region;

fabricating a contact region over said high-doped region in said resistor region of said polycrystalline silicon layer, said contact region being electrically connected to said resistor region.

**Claim 15 (original):** The method of claim 14 wherein said doping barrier comprises photoresist.

**Claim 16 (canceled).**

**Claim 17 (previously presented):** The method of claim 14 wherein said step of doping said polycrystalline silicon layer with a first dopant comprises doping said gate region.

**Claim 18 (original):** The method of claim 14 wherein said first dopant is an N type dopant.

**Claim 19 (original):** The method of claim 18 wherein said N type dopant comprises phosphorous.

**Claim 20 (previously presented):** The method of claim 14 wherein said first dopant comprises phosphorous at a dose of approximately  $6.5 \times 10^{15}$  atoms per square centimeter.

**Claim 21 (original):** The method of claim 14 wherein said second dopant is a P type dopant.

**Claim 22 (original):** The method of claim 21 wherein said P type dopant comprises boron.

**Claim 23 (previously presented):** The method of claim 14 wherein said second dopant comprises boron at a dose of approximately  $1.0 \times 10^{15}$  atoms per square centimeter.

**Claim 24 (canceled).**

**Claim 25 (currently amended):** The method of claim 24 14 wherein said contact region comprises a silicide.